

Fig. 1. The FE-SEM images of WO_3 film (a) $\times 30$ K, (b) $\times 100$ K.

when W^{5+} oxidizes to W^{6+} again. Therefore, it is possible to use this gasochromic characteristic to prepare a hydrogen sensor to detect the hydrogen concentration of a gas or to be used in gasochromic windows [20].

Among the preparation methods for WO_3 film, cathodic electrodeposition is simple, has the capability for mass production and is suitable for large area films. Therefore, electrodeposition was chosen for WO_3 film preparation in the present study. The hydrogen sensor was prepared by coating ITO glass with a layer of electrodeposited WO_3 film, followed by a layer of sputtered Pt film. Sensor properties of the WO_3/Pt films were investigated at room temperature in H_2 – N_2 gas mixtures containing 0–50 mol% of H_2 .

2. Experimentals

2.1. Preparation of substrate

Indium tin oxide (ITO) glasses ($15 \Omega/\square$, RITEK Corp., Taiwan) were used as the substrates for electrodeposition. The ITO glasses measured about $2.5 \text{ cm} \times 5 \text{ cm}$. All ITO glasses were cleaned with detergent soap, alcohol and de-ionized water before coating.

2.2. Preparation of electrodeposition solution

28% hydrogen peroxide (0.08 M, Union Chem. Co., Taiwan), H_2SO_4 (0.36 M, Union Chem. Co., Taiwan) and Na_2WO_4 (0.1 M, Sigma-Aldrich Inc. USA) were dissolved in de-ionized water to prepare the electrodeposition solution [22].

2.3. Preparation of gasochromic films and devices

A two-electrode cell system and constant potential technique were used in the electrodeposition process. ITO glass was used as the working electrode and platinum as the counter electrode. The deposition potential was controlled at -2.5 V and the deposition time was 500 s. After deposition, WO_3 film was dried at 80°C for 30 min to obtain the gasochromic film. The sensor device was then prepared by sputtering a layer of platinum with thickness about 20 nm over the WO_3 film. All experiments were performed at room temperature. The proposed coating conditions gave the best mechanical stability and optical response of the electrodeposited WO_3 in the present study.

2.4. Measurement of gasochromic films and devices

The surface morphologies, thicknesses and elemental compositions of WO_3 and WO_3/Pt films were examined by Field-Emission Scanning Electron Microscope with Energy Dispersive Spectrometer (FESEM-EDS, HITACHI S4800, Japan). The crystal structure and phase identification of the films were investigated by transmission electron microscopy (TEM, model JEOL II 1200EX, Japan) operated at 120 kV and X-ray diffractometry (XRD, Bruker AXS D8 DISCOVER Advance Diffractometer, Germany, Cu K_α radiation) with a grazing incidence of angle 1° . The accelerating voltage and the applied current were 40 kV and 300 mA, respectively. The colorations of the gasochromic devices

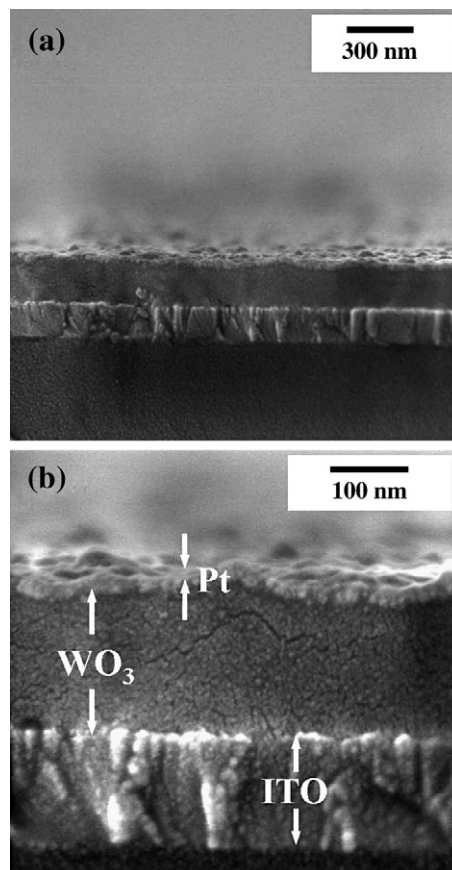


Fig. 2. The FE-SEM images of the cross-section of WO_3 film (a) $\times 30$ K, (b) $\times 100$ K.

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